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PATENT 1084D01T9320 016301-009320

Assistant Commissioner for Patents

Washington, D.C. 20231

on Flbruary 25, 2002

TOWNSEND and TOWNSEND and CREW LLP

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Thre application of:

David Cheung et al.

Application No.: 09/418,818

Filed: October 15, 1999

For: METHOD AND APPARATUS FOR DEPOSITING ANTIREFLECTIVE

COATING

Examiner:

Rudy Zervigon

Art Unit:

1763

AMENDMENT



Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

In response to the Office Action mailed October 23, 2001, please amend the aboveidentified application as follows:

IN THE CLAIMS:

Please amend claim 4 as follows. The remaining claims are unamended, but are reproduced below for the Examiner's convenience and reference.

- 1. A substrate processing system, comprising:
- a vacuum chamber;
- a substrate supporter, located within the vacuum chamber, for holding a substrate;
- a gas manifold for introducing process gases into the chamber;
- a gas distribution system, coupled to the gas manifold, for distributing the process gases to the gas manifold from gas sources;